



# High Five: UHV SIMS with Plasma Primary & simultaneous positive and negative secondary ion detection

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# High Five: UHV SIMS with Plasma Primary & simultaneous positive and negative secondary ion detection

- Why Simultaneous positive negative ion detection
- Previous work
- Requirements for a new instrument
- Plasma FIB ion source
- SIMS detectors
- In-operando measurements

#### Why use Simultaneous Detection?

#### **Problems with quasi simultaneous analysis**

Changing extractor polarity within an experiment causes deflection of the primary beam and makes image registration and depth profiling difficult – this is especially true for FIB applications where crater sizes are smaller than the shift!

It takes significant time (seconds) to change and stabilise the secondary column potentials

Residual gas deposition – oxygen – may interfere with isotopic diffusion studies

#### True Simultaneous collection

Allows collection of spatially identical regions for positive and negative ions with accurate image registration.

#### Where is this useful?

#### 1) Energy conversion and storage

Understanding and optimisation of the ionic processes taking place in bulk materials surfaces and interfaces of solid oxide fuel cells (SOFC), electrolysers (SOE) and solid state Li batteries (SLIB).

#### 2) Engineering alloys

Study of subsurface oxygen. Evaluation of corrosion cracking with focus on the interaction of H with the surface and H grain boundary migration.

Use isotopically pure deuterium and oxygen-18 and Lithium to understand transport.

## ANALYTICAL

#### **Previous work**

#### - FEI FIB 200 with two SIMS detectors

Hiden EQS SIMS detector

& Residual gas

analyser

SED: gridded Channeltron

Micro-probe Needle Connectors

Gallium beam

FEI quadrupole mass filter SIMS detector



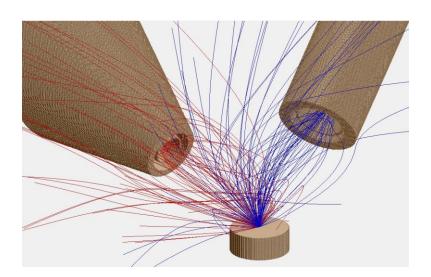
R. J. Chater, B. A. Shollock, D. S. McPhail, A. J. Smith and G. Cooke, Surf. Interface Anal., 2014, 46, 372–374.

R. J. Chater, A. J. Smith and G. Cooke, J. Vac. Sci. Technol. B, Nanotechnol. Microelectron. Mater. Process. Meas. Phenom., 2016, 34, 03H122.

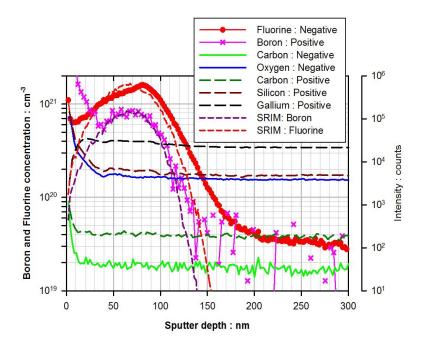


#### Simultaneous detection on FIB 200

Simion model of secondary ion collection



### BF<sub>2</sub> Implant into Silicon depth profiled using Ga primary ions





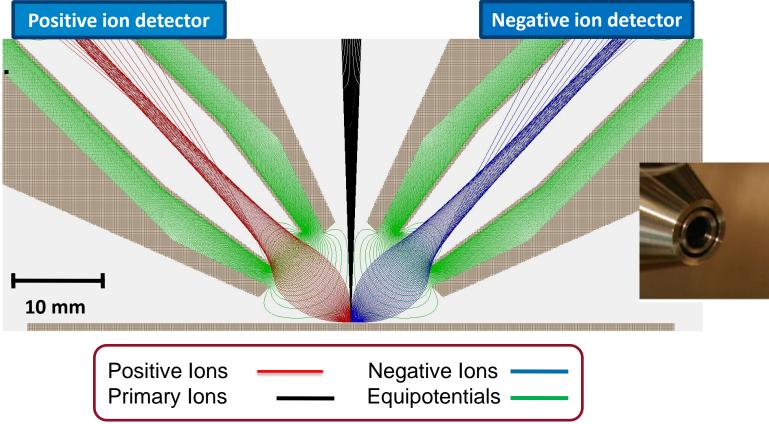


#### 5 Requirements for a New Instrument

Need SIMS for the low mass detection H, Li and O.

- 1. Simultaneous positive and negative ion detection two detectors
- 2. High ion yields and fast analysis time 30 nm plasma FIB with Oxygen capability
- 3. In situ processing chamber cleaning and sample prep
- 4. In-operando analysis ability to bias and temperature cycle
- 5. UHV Lithium is very sensitive to oxidation!





- SIMION ray-tracing model of a configuration for SPN secondary ion detection with two Hiden EQS detectors
- Sputtering by a normally incident primary beam.
- Opposing balanced symmetrical fields enhance high collection efficiency





## Hi5 SIMS Instrument

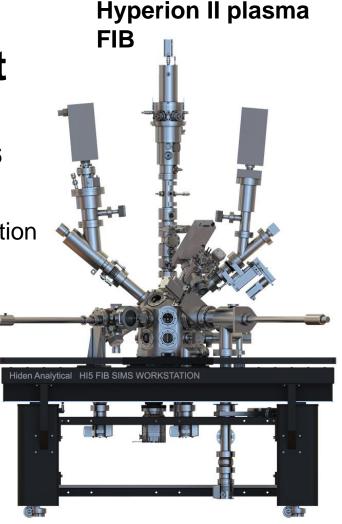
20 mm HMR quadrupole SIMS analyser

Charge compensation electron gun

Loadlock 1

UHV high stability chamber

5 axis stage



9 mm quadrupole SIMS analyser

Secondary Electron detector

IG5C caesium ion gun (Cs flood for –ve ions)

Loadlock 2 and process chamber

Anti-vibration table







Hi5 SIMS: Imperial College, Materials Dept., Surface Analysis Facility. Full primary column build, November 2021. (Noel Smith, Oregon Physics)









Hi5 SIMS: UHV chamber configuration for 10mm working distance 5-Axis stage and Kleindiek piezo probes, base pressure ~5e-9mbar



#### Hyperion II – *Plasma source parameters*



- 0 to ±30kV (except Neon & Helium, which is 0-10kV)
- Spot size 30 nm FWHM
- Typically operates with Xenon, Argon, Neon, Helium or Oxygen
- Energy Normalized Brightness
  - + ions Xenon: 1x10<sup>4</sup>, Oxygen: 4x10<sup>3</sup>, Helium: 6.5x10<sup>3</sup> Am<sup>-2</sup>sr<sup>-1</sup>V<sup>-1</sup>
  - ions Oxygen: 3x10<sup>2</sup> Am<sup>-2</sup>sr<sup>-1</sup>V<sup>-1</sup>
- Axial Energy Spread : 5eV (+ ions), 3.5eV (- ions)
- Lifetime > 2 years (+mode), >2000 hours (-mode)
- Stability <1% drift/ hour, <5% drift/24 hours</li>

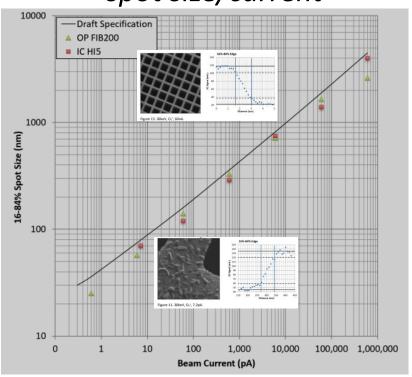


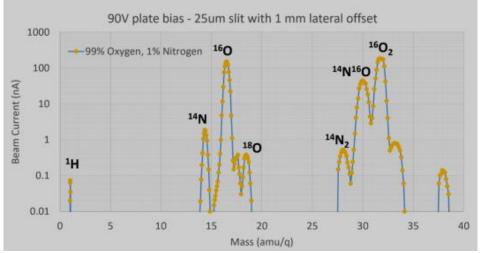
### Hyperion II – Plasma column performance

30keV Oxygen beam:

spot size/current

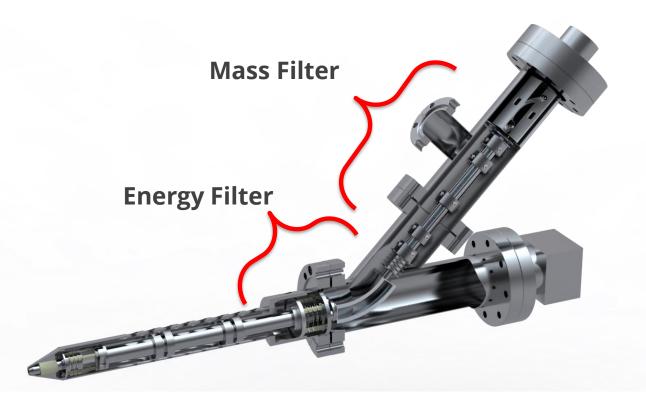
mass filter ( $M/\Delta M=37.5$ )







**Hiden EQS:** – On-axis sampling, energy resolving mass spectrometer for mass spectra with full 10<sup>6</sup> cps dynamic range of channeltron detector





Easily fits to other surface analysis instruments and FIB tools, eg Zeiss Nvision X-beam with EQS



#### DLS-20 Mass Filter – 20mm pole diameter Operates in both first and second stability region





## Only the Resolving Power of Zone II gives ultimate detection limit for He in D<sub>2</sub>

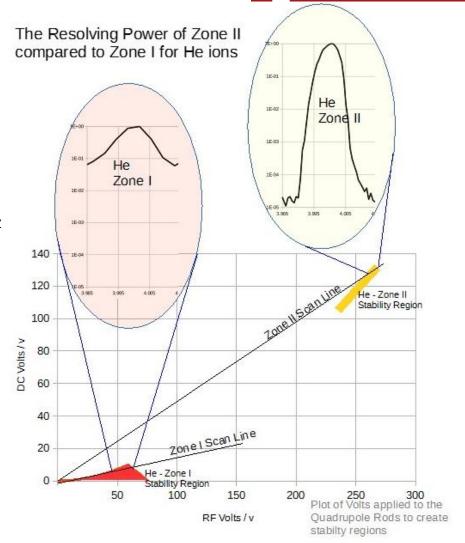
Quadrupoles operate with RF and DC Voltages applied to their rods which then carry ions to the detector

Certain voltage combinations can create 'stability regions' that transmit only ions of a particular m/z Scanning the Quad's Voltages across the tips of these regions will carry only that ion to the detector

The Zone I region is most often used. However, a second region, Zone II, offers much greater Resolving Power – which helps separate adjacent masses

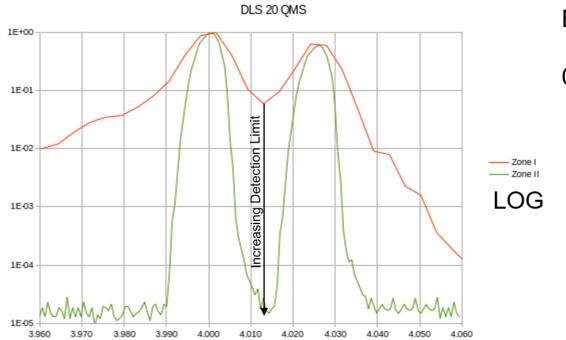
But only Quadrupole Electronics with both high power and stability can operate in this Zone Hiden's High Power Electronics is now offered with selectable Zone I and II capability.

## Switching time between zones typically 100ms.





Detection Limits for He in  $D_2$  depend on the Resolving Power of the Quadrupole. The benefits of operation in Zone II are clearly demonstrated – detection limit enhanced by almost four orders of magnitude!

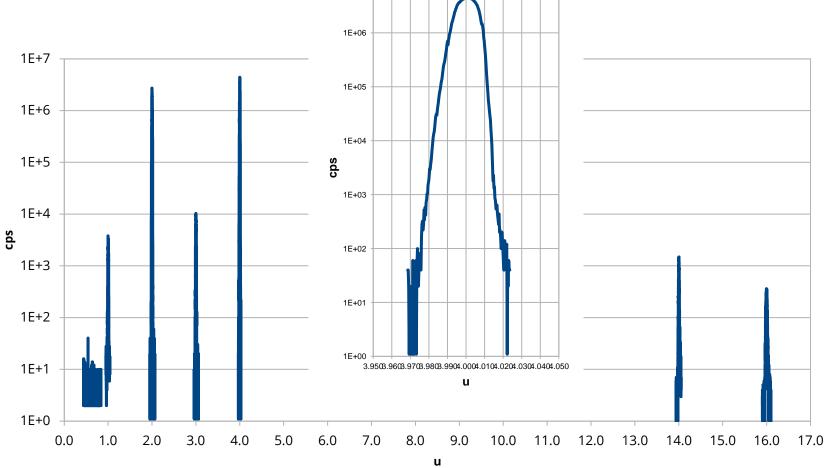


Best FWHM to date

0.002 amu







He+

1E+07



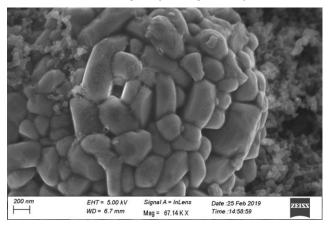
London

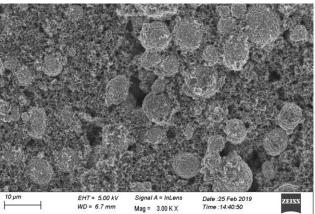
#### Hi5-SIMS: Lithium ion solid state battery cathode

 $Li(NiO_{0.8}Mn_{0.1}Co_{0.1})O_2 + conductive carbon + PVDF binder (NMC)$ 

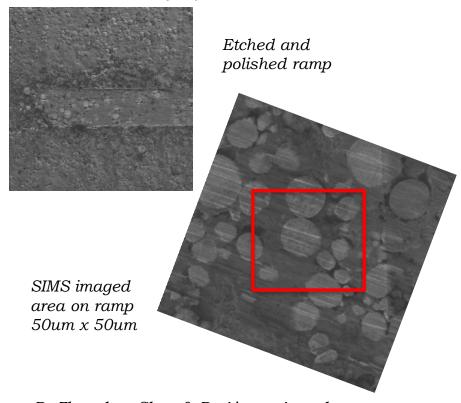
#### Rough surface prepared by etch and polish with xenon ion beam before SIMS

*SEM image of rough surface* 





Hi5 SED image of beam polished ramp



<u>Dr Zhonghao Shen</u> & Dr Ainara Aguadero Partners in the Faraday Institution Degradation Project



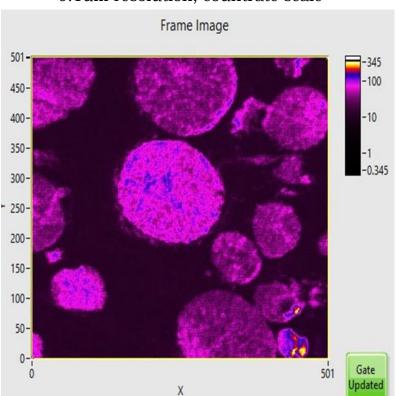
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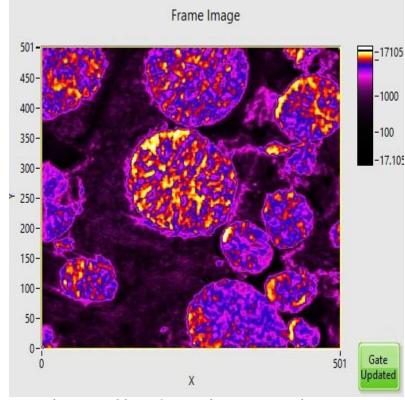
 $Li(NiO_{0.8}Mn_{0.1}Co_{0.1})O_2 + conductive carbon + PVDF binder (NMC)$ 

#### Simultaneously mapped area with 100 nm pixel resolution

Negative SIMS image O16<sup>-</sup>, 50um area, 500 x 500 pixels, 0.1um resolution, countrate scale



Positive SIMS image Li7+, 50um area, 500 x 500 pixels, 0.1um resolution, countrate scale



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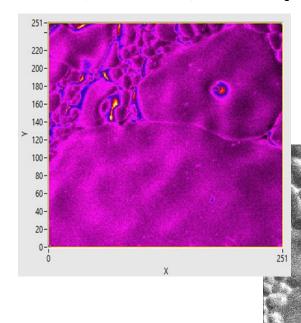
London

#### Hi5-SIMS: Lithium ion solid state battery cathode

Lithium-stuffed garnet, (NiO<sub>0.8</sub>Mn<sub>0.1</sub>Co<sub>0.1</sub>)O<sub>2</sub> (LLZO)

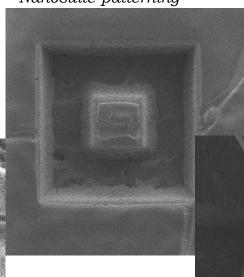
#### Grain boundary selection for in-situ electrochemical analysis

Negative SIMS image O16<sup>-</sup>, 250um area, 250 x 250 pixels

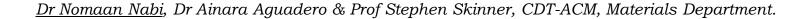


Total positive secondary ion image

Pillar structure using Xenon beam patterning with Raith Nanosuite patterning



Microprobe contacts to pillar for Electrochem analysis of grain boundary







#### Conclusion

Hi5 is a simultaneous positive and negative UHV plasma FIB-SIMS instrument specifically aimed energy storage, corrosion and fuel cell applications.

It also has micro-machining capability for sample preparation and chambers for isotopic diffusion studies.

A High mass resolution Quadrupole operating in first AND second stability regions reduces the effects of mass intereference.

Heating, cooling and electrical contacts enables In-operando analysis for real time evaluation of the sample.